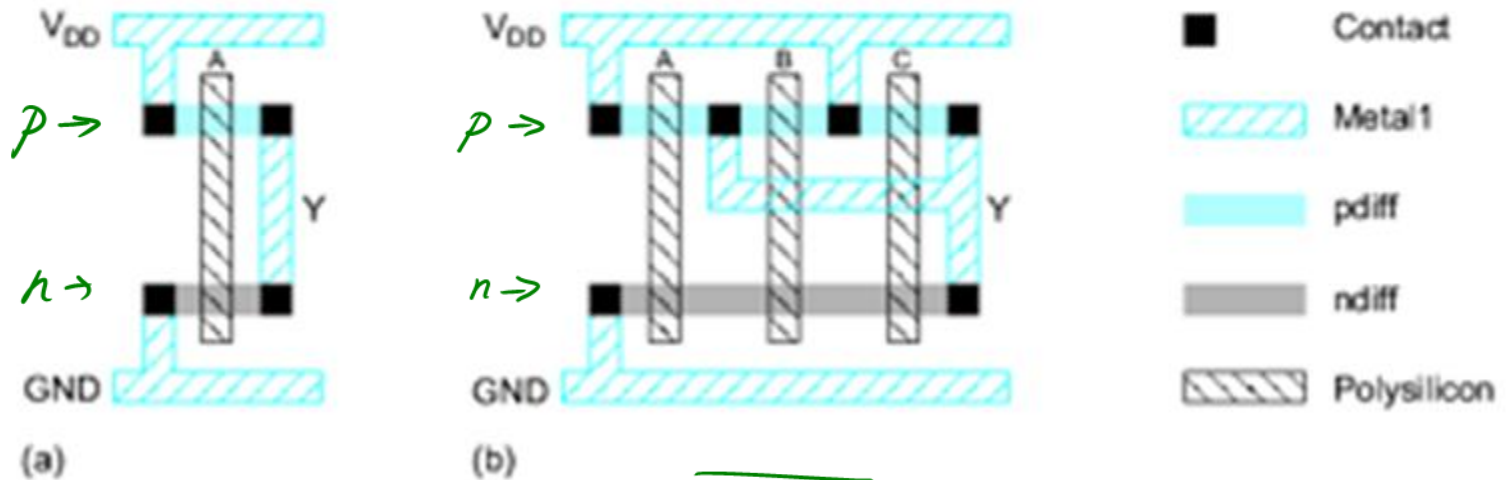


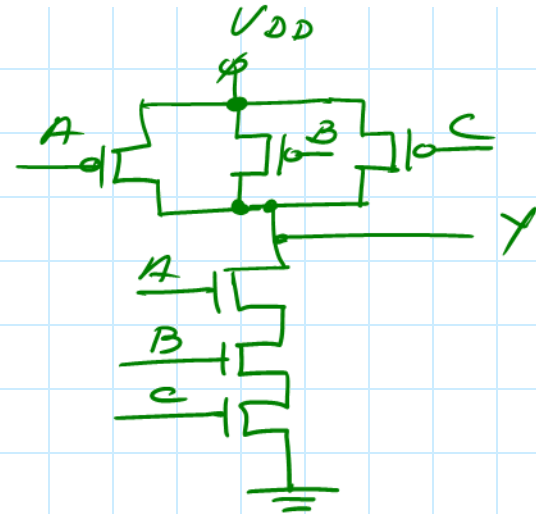
# UNIT 4. CMOS

5.1. Indicate the logic function that implements the standard cell with the layouts of the figure:



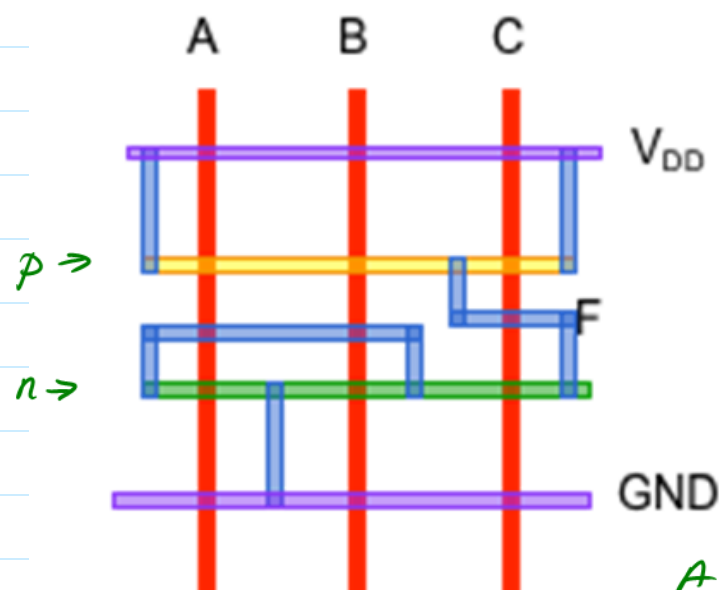
$$Y = \overline{A}$$

$$Y = \overline{A \cdot B \cdot C}$$

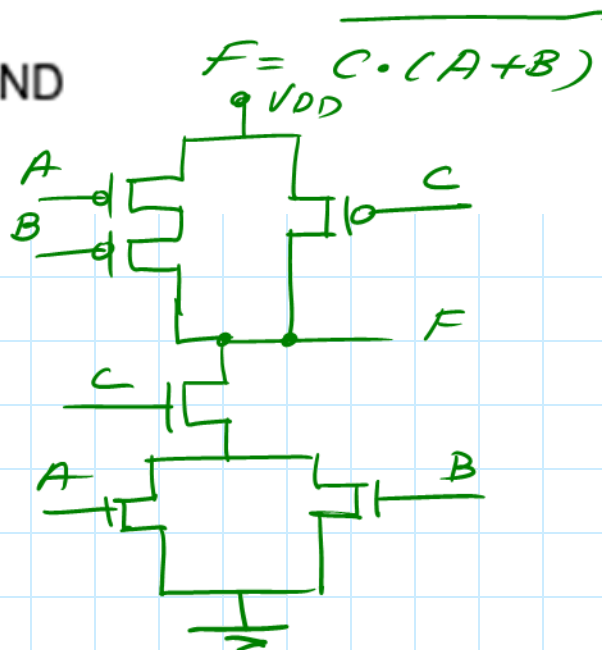


## UNIT 4. CMOS

5.2. From layout diagram of the figure, indicate the logic function that implements the standard cell.



Violet → metal 2 ( VDD y GND)  
Blue → metal 1 (internal connections)  
Green → N-diffusion  
Yellow → P-diffusion  
Red → polysilicon (transistor gates)



## UNIT 4. CMOS

5.3. Indicate whether they are true (V) or false (F) the following statements on the photolithographic manufacturing process of CMOS IC:

- a) Usually, a circular silicon wafers are used as substrate ✓
- b) Each wafer contains a single chip ✗
- c) They are deposited layers (layers) of different materials in a bottom-up way ✓
- d) The typical order in the deposition of layers is: 1) n + and p + areas of S and D, 2) metal interconnections, 3) thin insulating layer of gate, 4) polysilicon of the gate ✗ → metal at the end
- e) UV light is used to project the masks on the wafer ✓
- f) Once you have the chips on the wafer substrate, they are cut, tested and encapsulated ✓

5.4. If we compare the standard cell based design with full-custom design, we can say that:

- A) The semi-custom design based on cells optimizes the speed and silicon occupied area. ✗
- B) The full-custom design is getting more automated, minimizing the design time ✗
- C) The full-custom design is done with layout editors, making the geometric description of the masks ✓
- D) In the cell design, the smallest units of design are the transistors, which are stored in libraries ✗

## UNIT 4. CMOS

3.4. The figure shows 8 open-drain outputs connected to a bus. Only one gate is enabled at a time, remaining the other with a high level at the output. Indicate the maximum and minimum pull-up resistor  $R$ , according to the following specifications of the logic gates:

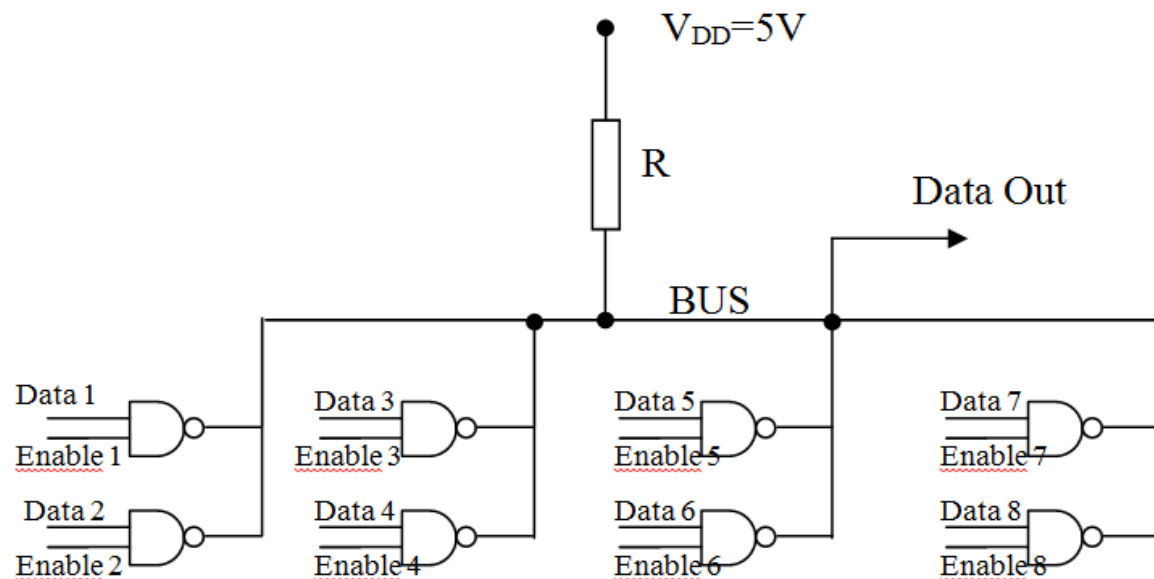
(74HC gates specifications):

$$I_{OLmax} = 4mA,$$

$$V_{OLmax} = 0.33V$$

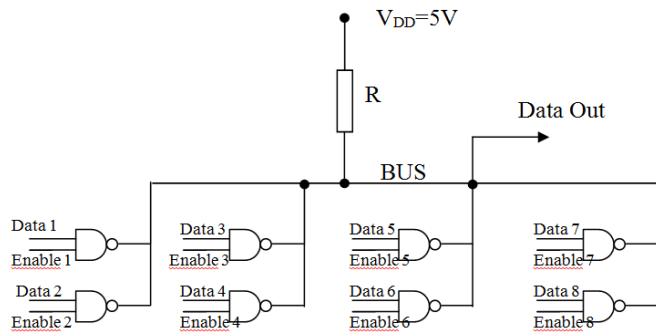
$$V_{OHmin} = 3.84V$$

$$I_{OHmax} = 5\mu A \text{ (leakage current at the output when High)}$$



- A)  $0.5K \leq R \leq 4K7$
- B)  $0.5K \leq R \leq 10K$
- C)  $1.5K \leq R \leq 3K3$
- D)  $1.17K \leq R \leq 29K$**

# UNIT 4. CMOS



$$m = 8; n = 0$$

$$\frac{V_{DD} - V_{OLmax}}{I_{OLmax} - n I_{ILmax}} \leq R \leq \frac{V_{DD} - V_{OHmin}}{m I_{OHmax} - n I_{IHmax}}$$

$$\frac{5 - 0.33}{4} \leq R \leq \frac{5 - 3.84}{8 \cdot 0.005}$$

$$1.168K \leq R \leq 29K$$